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AF/1752

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : Confirmation No. 9938  
Hiroshi TAKANASHI et al. : Docket No. 2001-0476  
Serial No. 09/838,118 : Group Art Unit 1752  
Filed April 20, 2001 : Examiner S. Lee

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NEGATIVE-WORKING PHOTOSENSITIVE  
RESIN COMPOSITION AND PHOTOSENSITIVE  
RESIN PLATE USING THE SAME

THE COMMISSIONER IS AUTHORIZED  
TO CHARGE ANY DEFICIENCY IN THE  
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ACCOUNT NO. 23-0975.

AMENDMENT AFTER FINAL

Assistant Commissioner for Patents,  
Washington, D.C.

RESPONSE UNDER 37. CFR 1.116  
EXPEDITED PROCEDURE  
EXAMINING GROUP 1752

Sir:

This in response to the Final Rejection dated April 26, 2002.

REMARKS

Favorable reconsideration is requested.

The claims are 1-4.

Claims 1-4 are rejected under 35 USC §103(a) as being unpatentable over Kashio et al. (US 5,688,632) in view of Nishimiya et al. (US 6,030,748).

The rejection holds that the present invention is obvious from Kashio in view of Nishimiya on the ground that Kashio teaches components (A) - (D) of the present invention and Nishimiya teaches incorporation of benzoic acid for the purpose of increasing sensitivity of the composition, the benzoic acid corresponding to component (E) of the present invention, and that therefore incorporation of benzoic acid disclosed by Nishimiya into a composition disclosed by Kashio is obvious to those skilled in the art.